

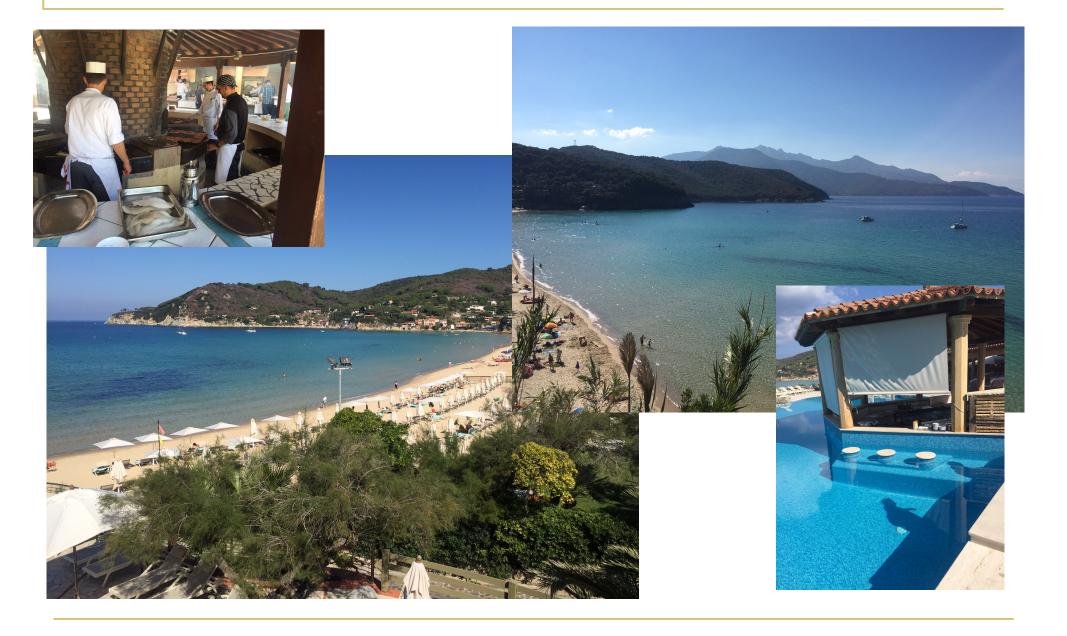


A selected summary of VERTEX2016

(CLIC-relevant highlights)

Daniel Hynds

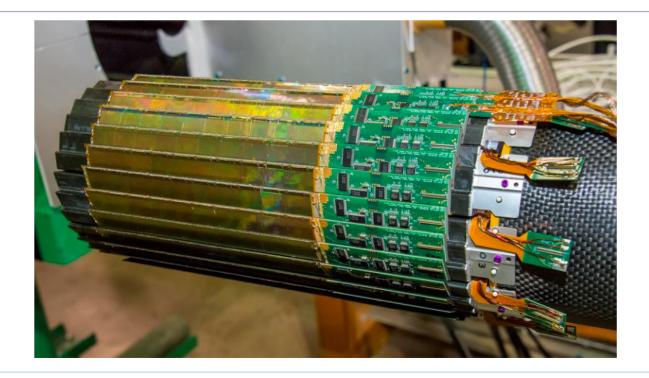
Elba...







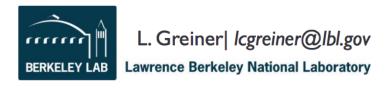
Operational Experience of the STAR MAPS Vertex Detector



Leo Greiner for the STAR Collaboration

Lawrence Berkeley National Laboratory

VERTEX 2016 - 25th International Workshop on Vertex Detectors La Biodola, Isola d'Elba, Italy, 25-30 September 2016





PXL Design Parameters

DCA Pointing resolution	(10 ⊕ 24 GeV/p·c) μm	
Layers	Layer I at 2.8 cm radius	
	Layer 2 at 8 cm radius	
Pixel size	20.7 μm X 20.7 μm	
Hit resolution	3.7 μm (6 μm geometric)	
Position stability	5 μm rms (20 μm envelope)	
Material budget first layer	$X/X_0 = 0.39\%$ (Al conductor cable)	
Number of pixels	356 M	
Integration time (affects pileup)	185.6 μs	
Radiation environment	20 to 90 kRad / year	
	2*10 ¹¹ to 10 ¹² IMeV n eq/cm ²	
Rapid detector replacement	< I day	

- 356 M pixels on ~0.16 m² of Silicon
- Air cooling
- Sensors thinned to 50 µm



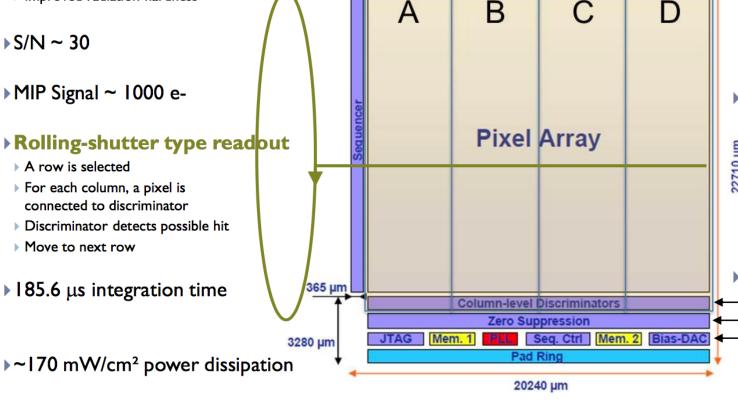
PXL MAPS sensor

Ultimate-2: third revision sensor developed for PXL by the PICSEL group of IPHC, Strasbourg AMS OPTO 0.35 process ionizing particle passivation Binary readout of hit pixels oxide 4 sub-arrays to help with process variation ▶ High resistivity p-epi layer Selectable analog outputs - 220 µm for Pads + Electronics p-epi ▶ Reduced charge collection time Improved radiation hardness p++ substrate A recombination **▶ Pixel matrix** \triangleright 20.7 µm x 20.7 µm pixels 928 rows x 960 columns = ~IM pixel Pixel Array In-pixel amplifier A row is selected In- pixel Correlated Double Sampling (CDS)



9/25/2016

- End-of-column discriminators
- Integrated zero suppression (up to 9 hits/row)
 - Ping-pong memory for frame readout (~1500 w)
- ▶ 2 LVDS data outputs @ 160 MHz



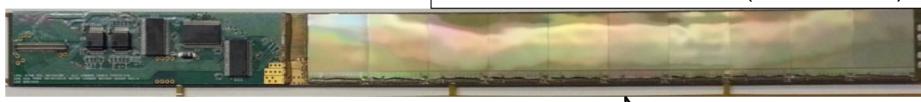
L. Greiner | lcgreiner@lbl.gov



PXL System Overview

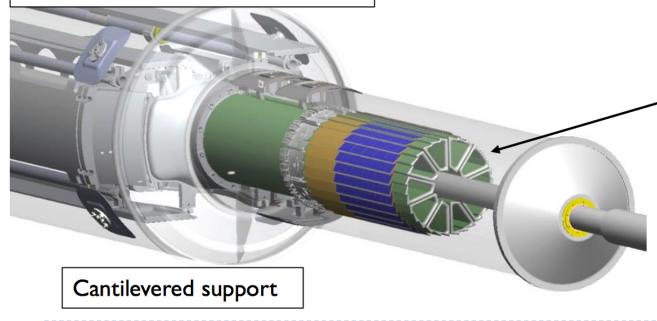
Basic Detector Element

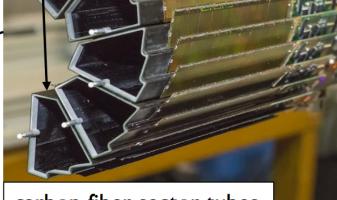
Ladder with 10 MAPS sensors (~ 2×2 cm each)



Mechanical support with kinematic mounts (insertion side)

10 sensors / ladder 4 ladders / sector 5 sectors / half 10 sectors total





carbon fiber sector tubes (~ 200 µm thick)



Operational Aspects

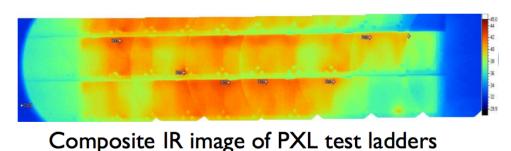
What worked well and what needed extra effort (after initial setup):

- Mechanics
 - The detector halves maintained survey pixel positions after insertion and during operational heating and in the cooling airflow (10 m/s).
 - The rapid insertion and removal mechanism worked allowing removal and replacement operation of a 2^{nd} detector in one day.
- Air cooling worked very well, typical variation in sensor temperature over the runs was within I-2 degree C.

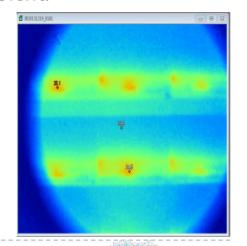


PXL Kinematic mounts

Sector vibration in the radial direction scales as:	flow ²
Sector vibration at full flow:	5 µm RMS
Sector DC displacement scales as:	flow ²
Sector moves in at full flow: (Stable displacement)	25 μm - 30 μm
Sector moves in when ladders powered: (Stable displacement)	3 μm - 8 μm



IR image of production PXL ladders. Max ΔT is 12° C from ambient.





Development and construction of the Belle II DEPFET pixel vertex detector

Vertex 2016, 25-30 September 2016

B. Schwenker for the DEPFET collaboration



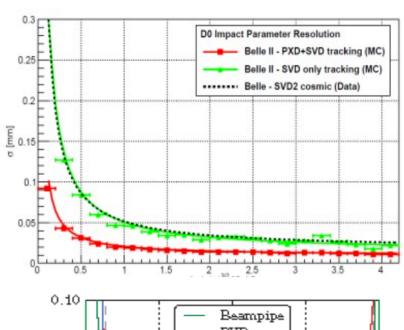




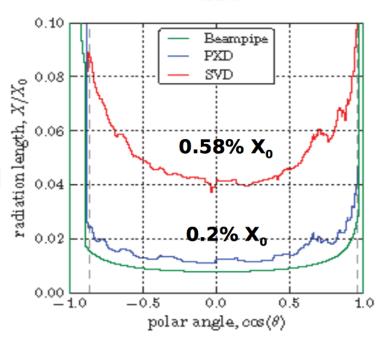


Belle II vertexing requirements

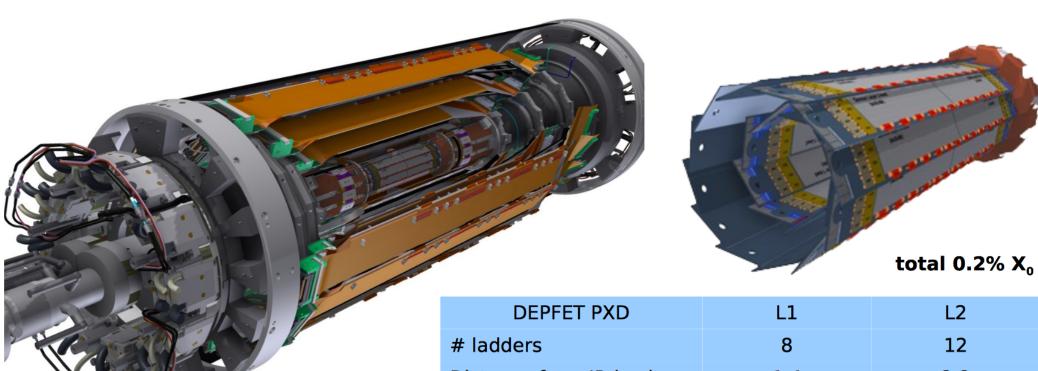
Radiation2 Mrad/year $2 \cdot 10^{12}$ 1 MeV n_{eq} per yearDuty cycle1Frame time20 μ sMomentum range50 MeV Acceptance17°-155°Material budget $0.2\% X_0$



- Modest impact paramter resolution (15 μ m), dominated by multiple scattering \rightarrow pixel size (50 x 75 μ m²)
- Lowest possible material budget (0.2% X)
 - Ultra-transparent detectors
 - Lightweight mechanics and minimal services



The Belle II vertex detector



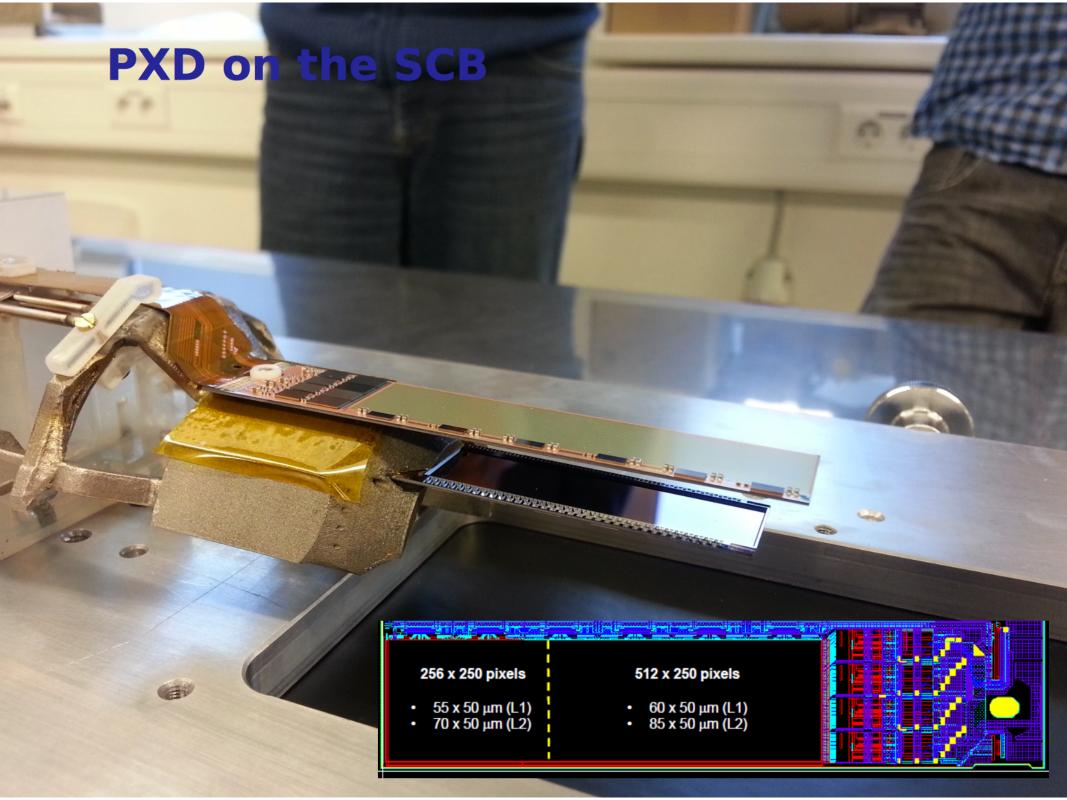
- 2 DEPFET layers (PXD)
- 4 Double Sided Si-Strip Detector layers (SVD)
- PXD + SVD integrationNov. 2017

L1	L2
8	12
1.4	2.2
75	75
768x250	768x250
3.072×10 ⁶	4.608×10 ⁶
55x50 60x50	70x50 85x50
50kHz/10MHz	50kHz/10MHz
89.6	176.9
	8 1.4 75 768x250 3.072x10 ⁶ 55x50 60x50 50kHz/10MHz

VXD Phase 2 hardware (Beast)

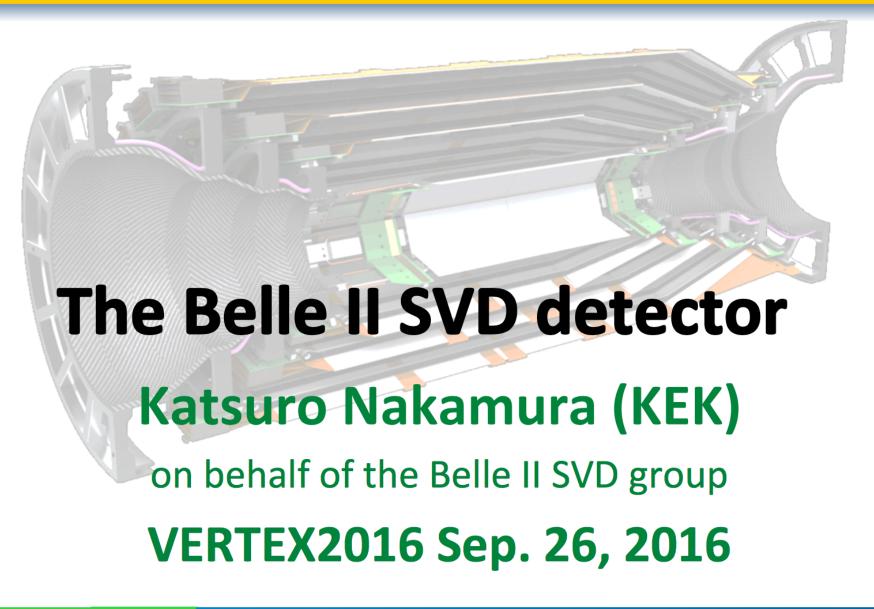
- Machine commissioning
- Radiation safe environment for the VXD
- 2 PXD and 4 SVD ladders
- +X direction, highest sensitivity to backgrounds





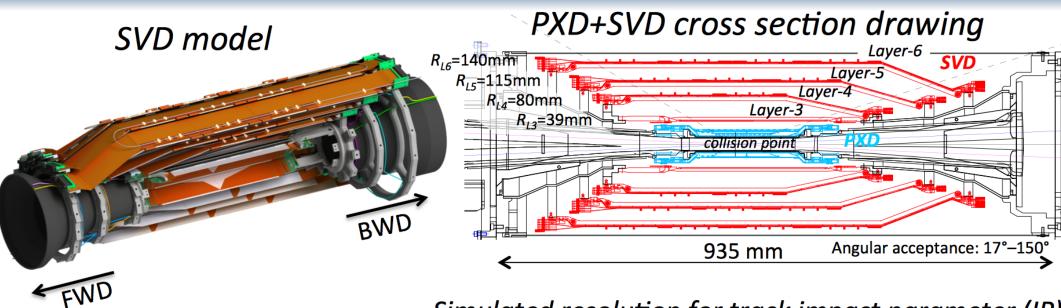






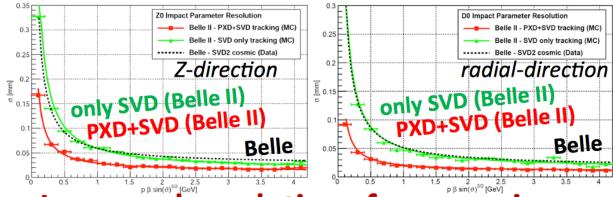
VERTEX2016

SVD Detector Overview



- 4 SVD layers (Layer-3 to -6) consist of ladders.
- The ladders are composed of several DSSD modules.
- Slant shapes in FWD region for the material budget reduction.
- Average material budget:
 0.7%X₀ per layer

Simulated resolution for track impact parameter (IP)

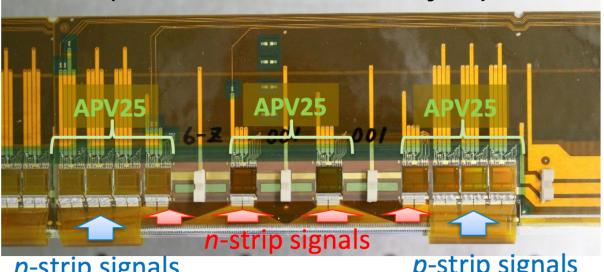


Improved resolutions from previous Belle experiment are expected.

 $\sigma_{IP} \sim 20 \text{um}$ at $p_T = 2 \text{GeV}/c$

Chip-On-Sensor Concept

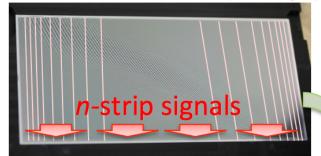
ORIGAMI flex (Si sensor is under the flex)



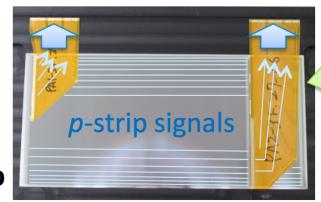
p-strip signals p-strip signals

- Flex circuit (ORIGAMI flex) is glued on sensor *n*-strip surface with an electrical/thermal-isolation foam.
- **APV25** are placed on the ORIGAMI flex to minimize the analog path length (capacitive noise).
 - Sensor strips and ORIGAMI flex are connected with Al wire-bonding (φ25μm).

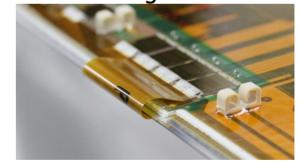
Sensor under ORIGAMI (n-strips)



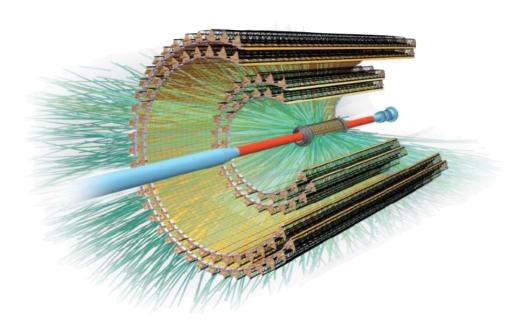
Sensor from other side (p-strips)



Wire bonding with Al wires.







The Upgrade of the ALICE ITS

Stefania Beolè

Università degli Studi di Torino & INFN

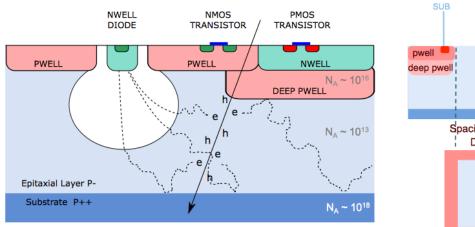
on behalf of the ALICE collaboration

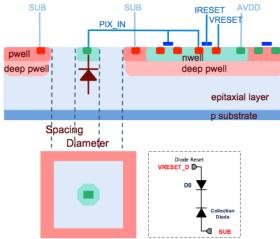






ALPIDE – Technology and Pixel Layout





CMOS Pixel Sensor - TowerJazz 0.18µm CMOS Imaging Process

- High-resistivity (> 1k Ω cm) p-type epitaxial layer (25 μ m) on p-type substrate
- Small n-well diode (2 μm diameter), ~100 times smaller than pixel => low capacitance (~fF)
- Reverse bias voltage (-6V < V_{BB} < 0V) to substrate (contact from the top) to increase depletion zone around NWELL collection diode
- Deep PWELL shields NWELL of PMOS transistors (full CMOS circuitry within active area)



Pixel Chip Requirements

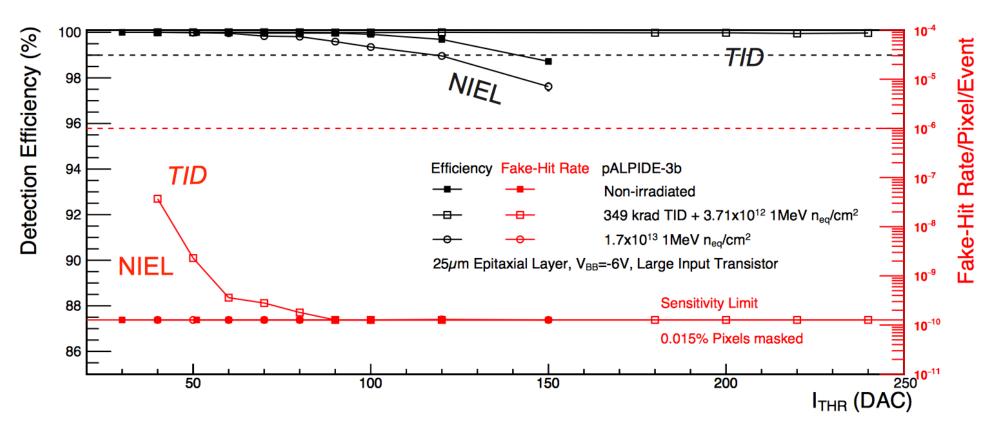
Pixel chip developed for the ITS Upgrade

Parameter	Inner Barrel	Outer Barrel	ALPIDE
Silicon thickness	50µm	100µm	✓
Spatial resolution	5µm	10µm	~ 5µm
Chip dimension	15mm x 30mm		✓
Power density	< 300mW/cm ²	< 100mW/cm ²	< 40mW/cm ²
Event-time resolution	< 30µs		~ 2µs
Detection efficiency	> 99%		✓
Fake-hit rate *	< 10 ⁻⁶ /event/pixel		<<< 10 ⁻⁶ /event/pixel
NIEL radiation tolerance **	1.7x10 ¹³ 1MeV n _{eq} /cm ²	10 ¹² 1MeV n _{eq} /cm ²	✓
TID radiation tolerance **	2.7Mrad	100krad	so far tested at 350krad

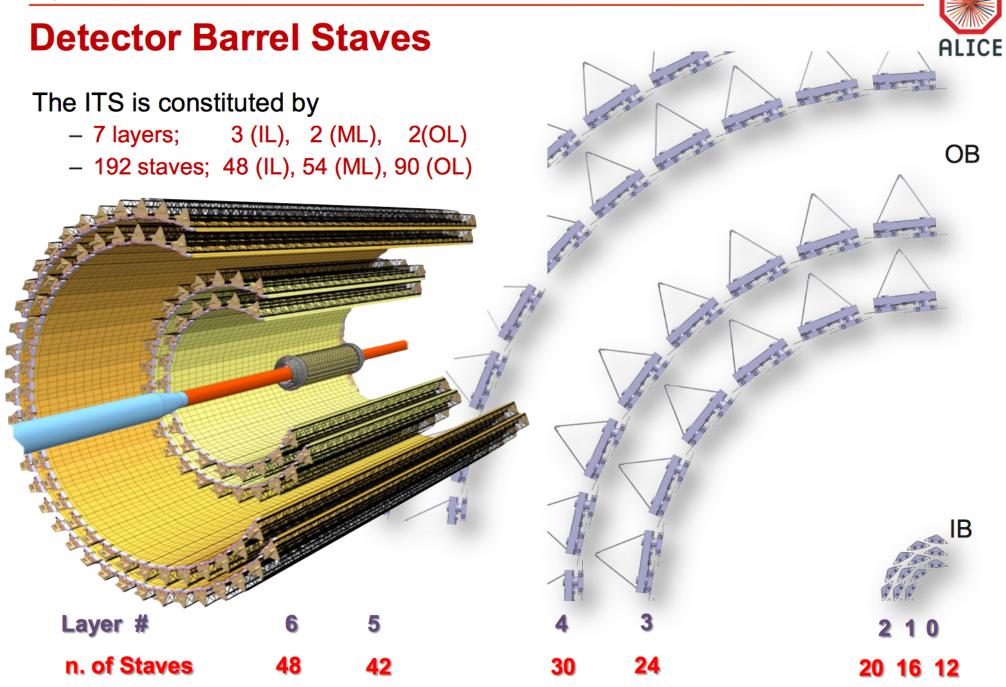
^{*} revised numbers w.r.t. TDR

^{**} including a safety factor of 10, revised numbers w.r.t. TDR

Test Beam Result of a Full-Scale ALPIDE Prototype (pALPIDE3): detection efficiency and noise occupancy

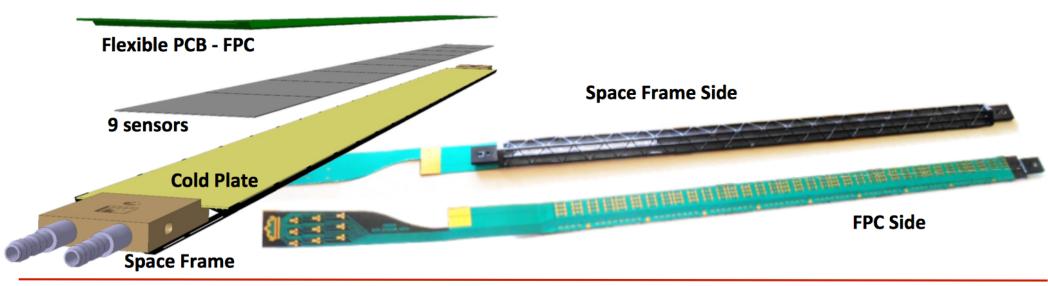


- Test beam Campaigns at PS (CERN), BTF (Frascati), DESY (Hamburg), Pohang (Korea) and SLRI (Thailand) – telescope made of pALPIDE3 sensors only
- Final pixel layout and front-end circuit selected
- Radiation effects visible
- Large operational margin maintained after NIEL and TID irradiation

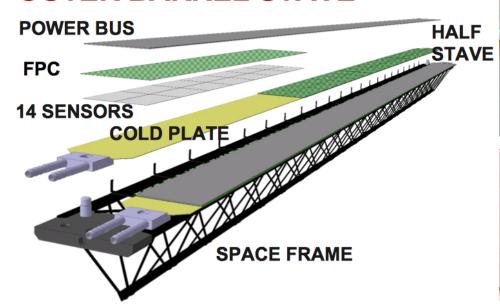


ALICE

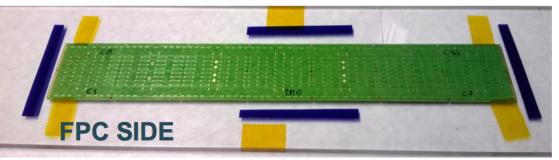
INNER BARREL STAVE



OUTER BARREL STAVE





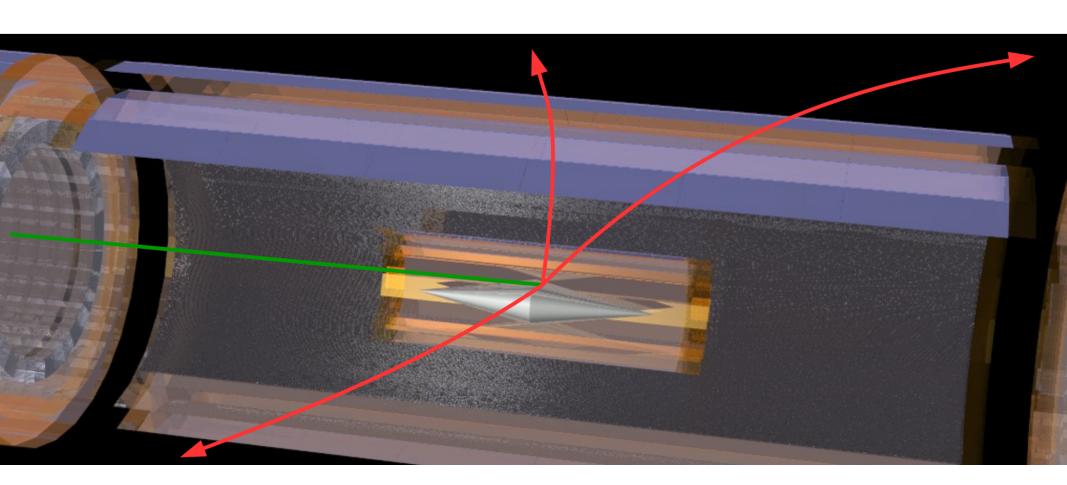




The Mu3e Pixel Detector

Vertex 2016, 26.-30. September, 2016

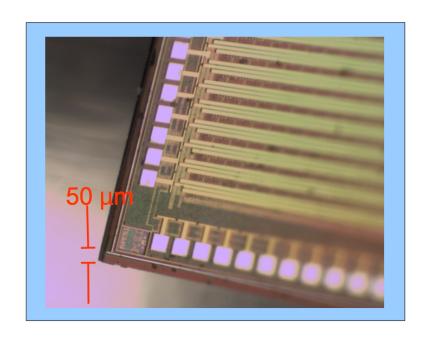
André Schöning
Physikalisches Institut, Universität Heidelberg



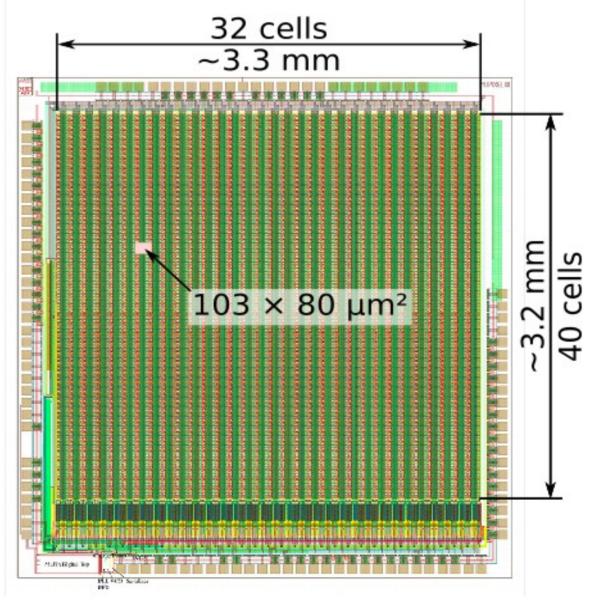


MuPix7 Prototype

Institutes: Heidelberg, Karlsruhe, Mainz



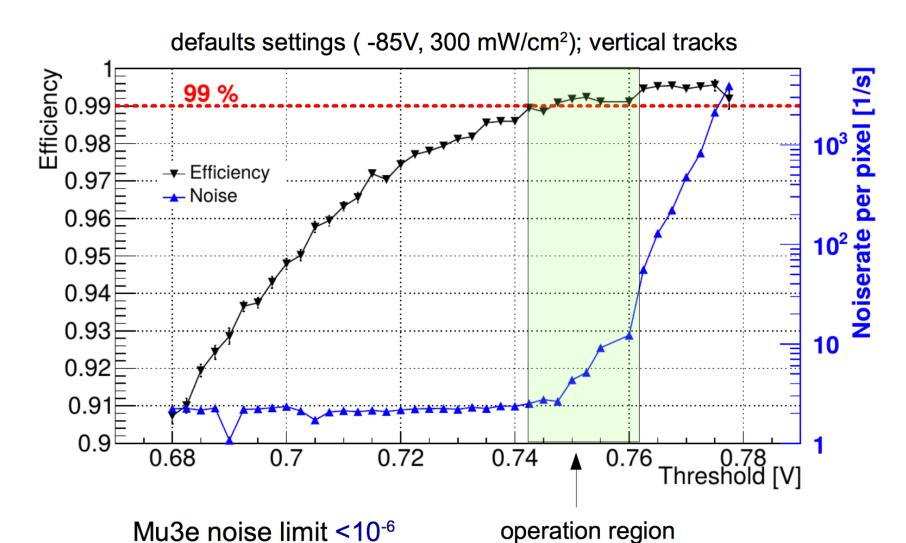
Austria Microsystems (AMS)
HV-CMOS 180 nm
20 Ωcm p-substrate





MuPix7 Efficiency and Noise

Data obtained from PSI beamtest (PiM1) using MuPix telescope

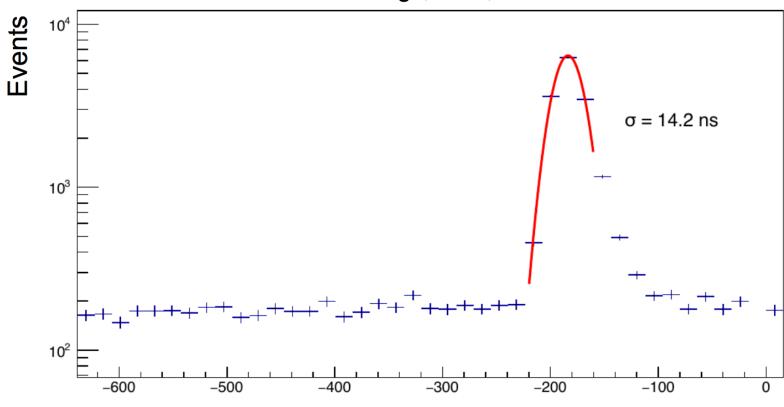




MuPix7 Time Resolution

MuPix telescope with scintillator as time reference:

default settings; -85V; 300 mW/cm²



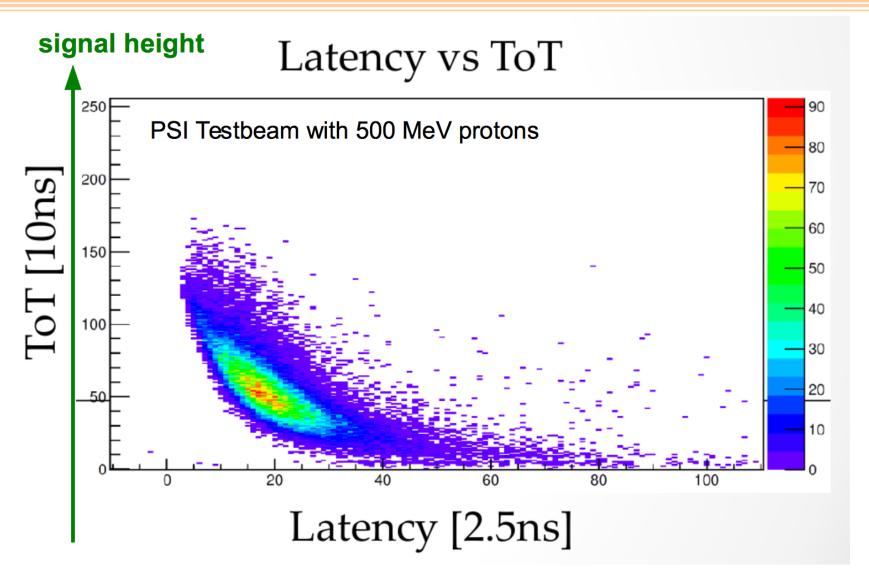
time difference wrt scintillator time (ns)

Mu3e requirement sigma (t) < 20 ns fulfilled

. .



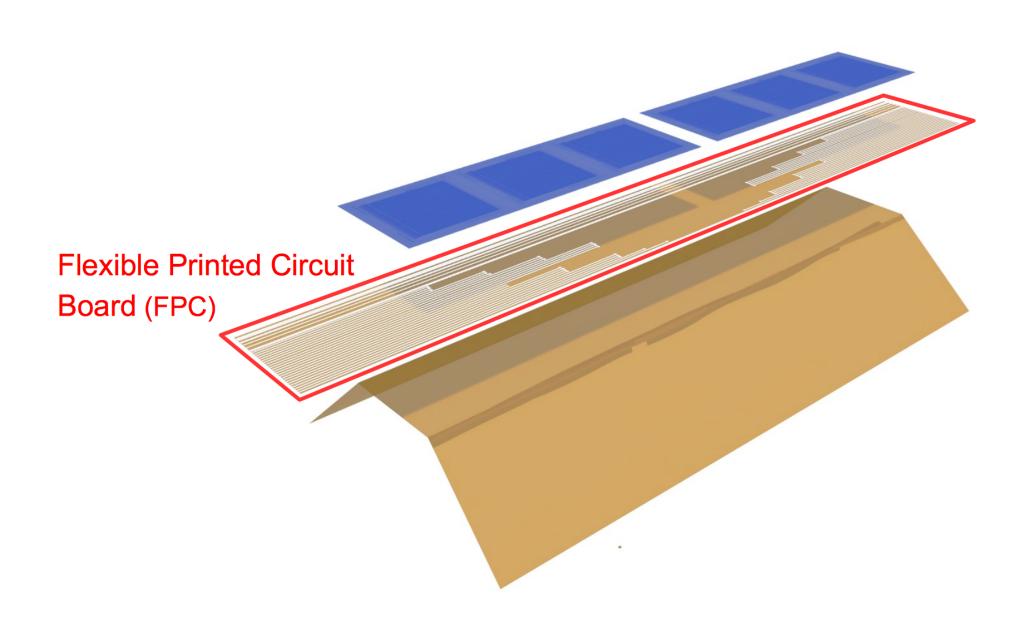
MuPix7 Time Resolution



- → timewalk correction possible
- \rightarrow in test chips sigma(t) ~ 5 ns achieved (I. Peric et al. KIT)



Mu3e Flexprint





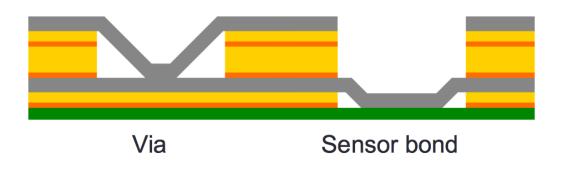
Mu3e Flexprint

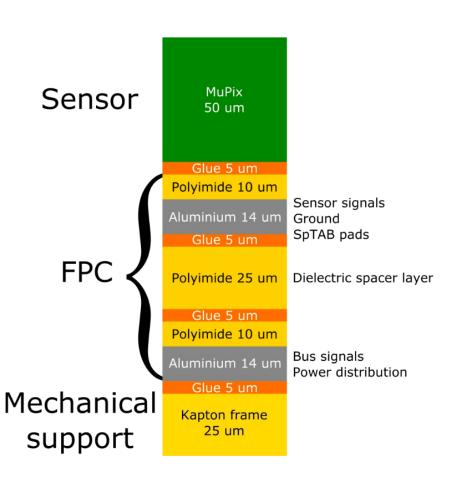
Two layer aluminium (LTU Ltd.)

- 14μm Al + 10μm polyimide per layer
- Structure sizes ≥ 65µm
- Dielectric spacing 45µm

SpTAB technology

- Single point Tape Automated Bonding
- No additional (high Z) material for bonding!







CMOS pixel development for HL-LHC

F. Hügging University of Bonn

VERTEX 2016
ELBA, ITALY







SOI Monolithic Pixel Detector Technology

Sep. 29, 2016, Vertex2016@Isola d'Elba, Italy

Yasuo Arai

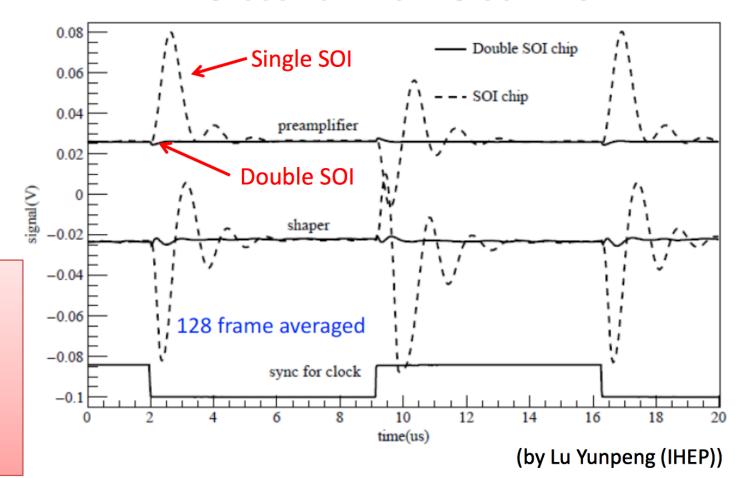
High Energy Accelerator Research Organization (KEK)

& The Okinawa Institute of Science and Technology (OIST)

yasuo.arai@kek.jp, http://rd.kek.jp/project/soi/

Effect of Double SOI

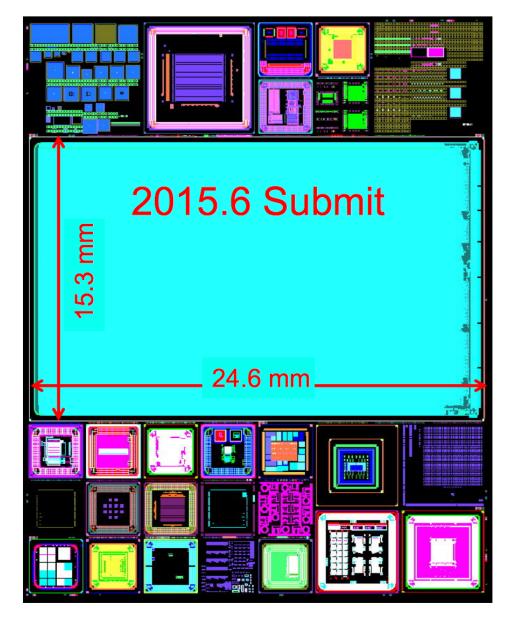
Cross Talk from Clock line

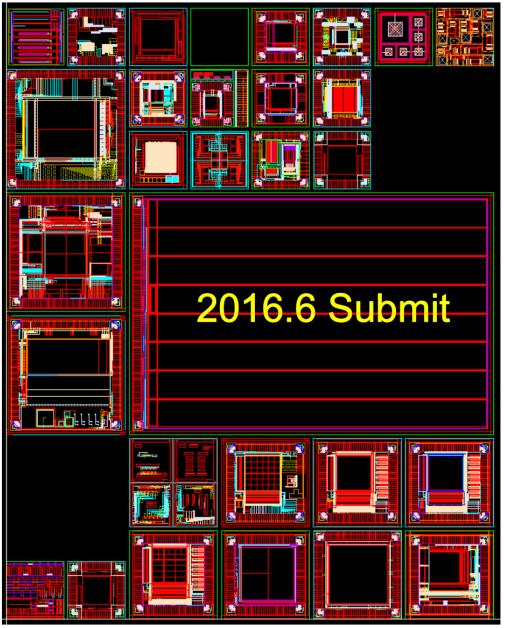


Shield: Cross Talk between Circuit and Sensor is reduced to 1/20.

Cross section of the Double SOI Pixel Middle Si Middle Si Metal 1 Contact ransistor Sensor Contact x9.0k TE 12/10/16 3.00 µm

KEK SOI Multi-Project Wafer run. (1~2 runs/year)

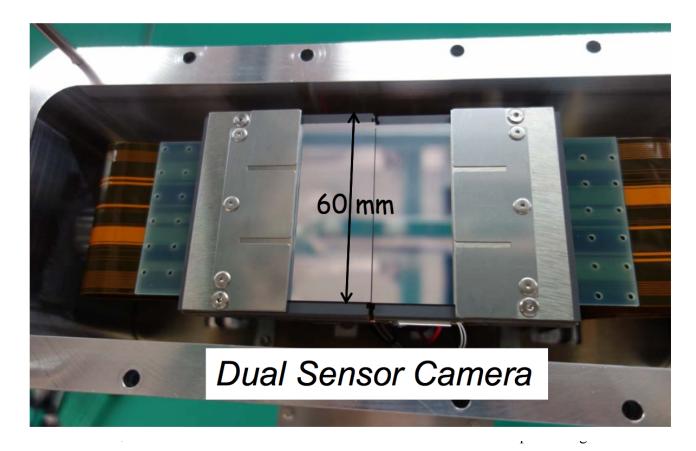




SOI Photon-Imaging Array Sensor (SOPHIAS) for X-ray Free Electron Laser (XFEL) SACLA

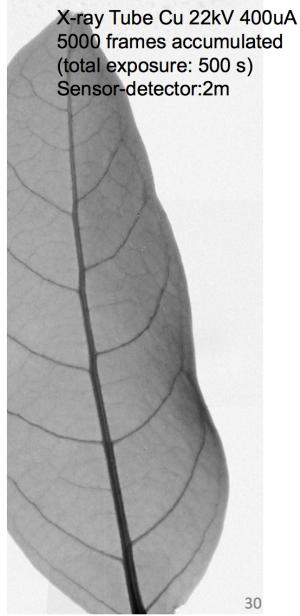
Utilization of SOPHIAS has been started for various experiments in SACLA@RIKEN.

- Dynamics of Atomic Structure
- Direct Observation of Chemical Reactions
- etc.

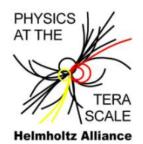














SPONSORED BY THE



The CMS Silicon Pixel Detector for HL-LHC

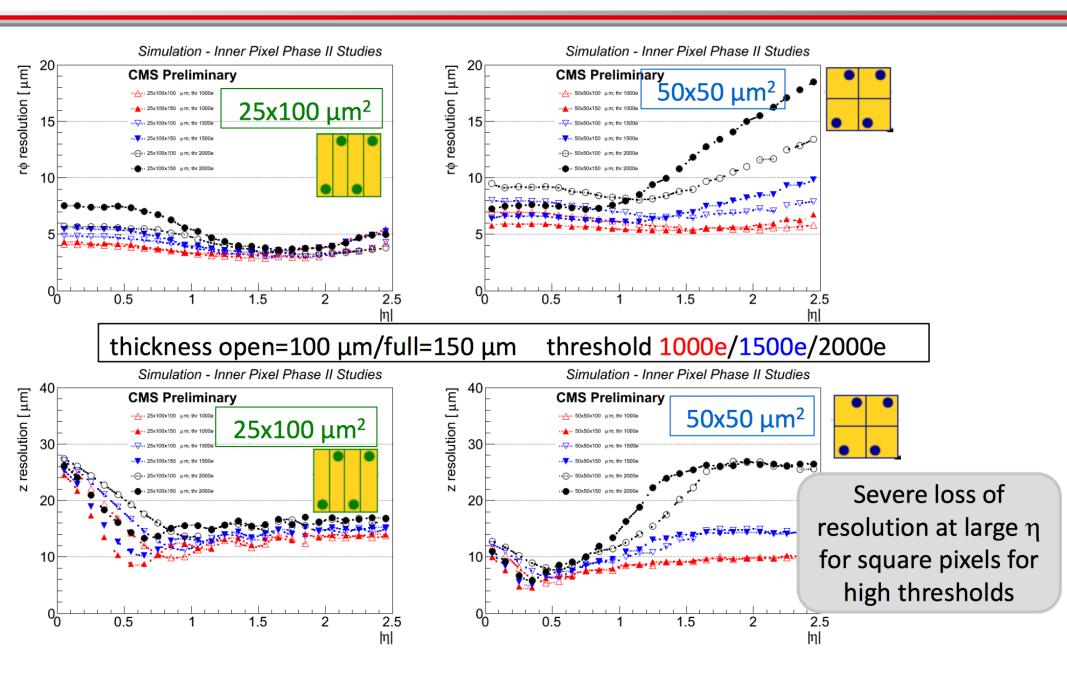
Georg Steinbrück, Hamburg University for the CMS Collaboration

Vertex 2016 September 25-30, 2016

La Biodola, Isola d'Elba, Italy



Fine Pitch Sensors



Vertical integration technologies for tracking detectors



Valerio Re



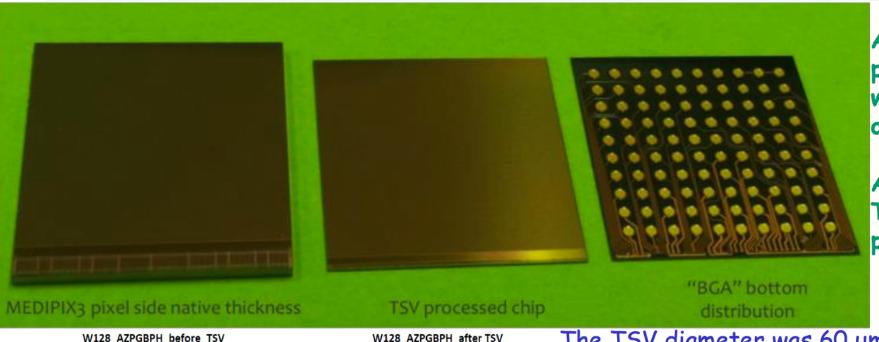
INFN Sezione di Pavia

Università di Bergamo

Dipartimento di Ingegneria e Scienze Applicate

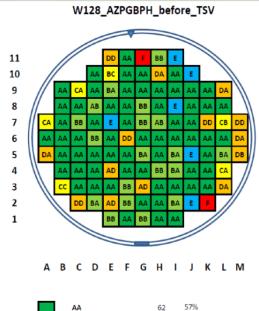


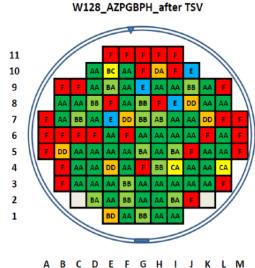
Low-density peripheral TSVs in the MEDIPIX chip



All IO logic and pads contained within one strip of 800µm width

All IO's have TSV landing pads in place





C2 and K2 were not received

The TSV diameter was 60 μ m (to match a wire bond pad pitch of roughly 100 μ m) and the wafers were thinned to 120 μ m for an optimised aspect ratio of 2.

TSV yield is adequate for small scale production; chip performance is preserved

Towards a new generation of pixel detector readout chips, M Campbell et al, IWORID 2015

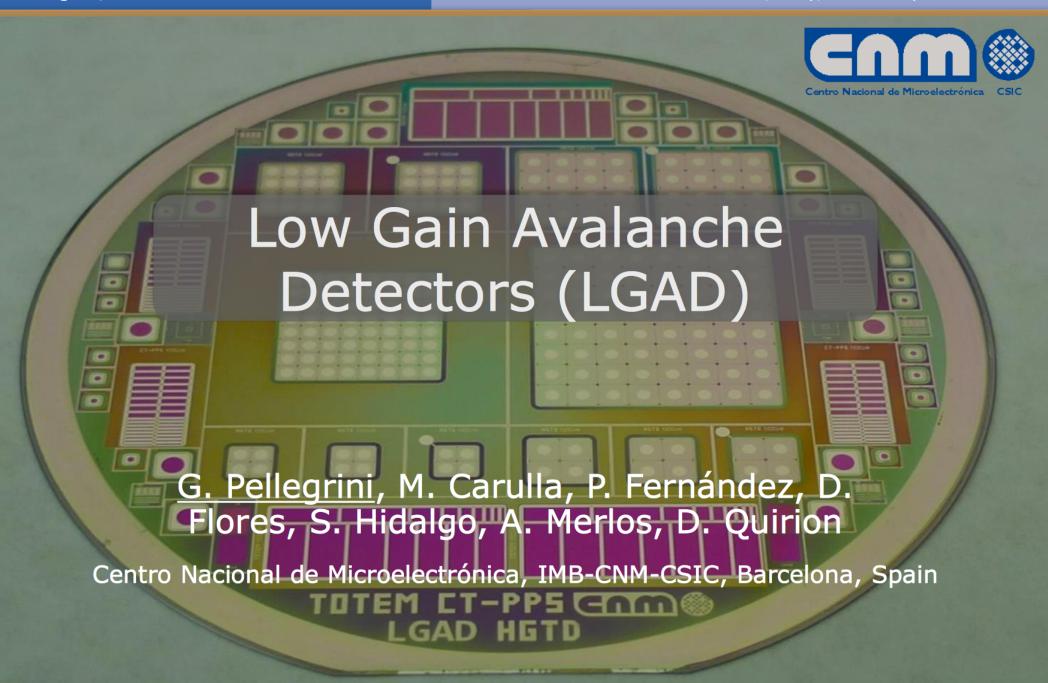
dola - September 30, 2016

3D integration for the next generation of MEDIPIX and TIMEPIX chips

TSV processing on 'ultra-thin' MEDIPIX3RX chips was also performed with good yield (wafers thinned to 50 μ m, TSV diameter 40 μ m), as a test of extremely thin assemblies primarily for vertex detector applications in high energy physics.

Next generation of 65 nm MEDIPIX4 (spectroscopic X-ray images at rates compatible with human CT) and TIMEPIX4 readout chips (sub-ns time stamping and reduced pixel pitch):

- in both chips the functions normally associated with the chip periphery will be located throughout the pixel matrix taking full advantage of the opportunities provided by the TSV process.
- as the readout logic is no longer confined to one chip edge there
 is more flexibility in the choice of readout architectures. The
 chips should be abuttable on 4 sides.







High Granularity Timing Detector

- > ATLAS is proposing Ultra Fast Silicon Detector (UFSD) based on LGAD as one of the technical options for the **High Granularity Timing Detector** (HGTD)
- ➤ High granular **timing detector** can provide a new capability in ATLAS to separate pileup from hard-scatter signals, provide pileup jet rejection, and improve e/g and jet reconstruction *
- > A **reduction of Substrate Thickness** from 300 μm to **50 μm** will reduce the Bulk Radiation Effects and will decrease the Collection Time.
- ➤ Integrate a Small Gain (10-30) in a sensor while maintaining similar Noise Levels and avoiding Readout Front-End saturation & Pile-up effects

4 active layers per side (~10 m² in total) in front of FCAL HGTD baseline dimensions:

 $Z = [3475, 3545] \text{ mm} ; \Delta Z = 70 \text{mm}$

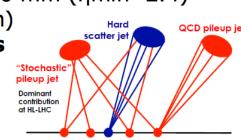
Rmin ~ 90 mm (η max ≈ 4.3), Rmax ~ 600 mm (η min ≈ 2.4)

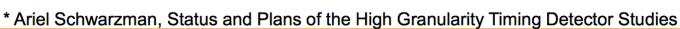
Possible to extend η =5.0 (Rmin ~ 50mm)

Required timing resolution: **50 – 100 ps**

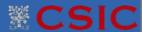
Radiation hardness= 5x10¹⁵n_{eq}/cm²

(preliminary)

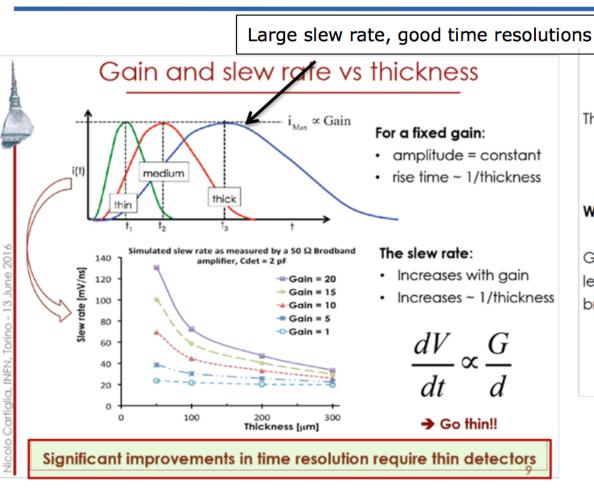








Why thin LGAD for timing?



What is the correct gain?

The answer at the root of the LGAD approach is:

The correct gain is the MINIMUM gain that does the job

Why?

Gain has obvious drawback in terms of much higher noise, higher leakage current, higher thermal load, segmentation, early breakdown...

The value of the "correct gain" does not exists it depends on the application.

N. Cartiglia. Signal formation and timing in LGAD sensors. Workshop on energy and time measurement with silicon devices. AIDA 2020 Annual Meeting. DESY. Hamburg. 13 June 2016

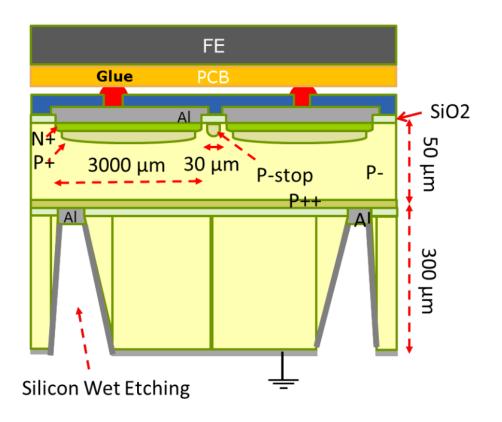
Goal is a detector that combines **excellent timing and position** measurement with very high rate capability (no dead-time after a hit). Specifically for timing, better than 40 psec measurement for a mip.

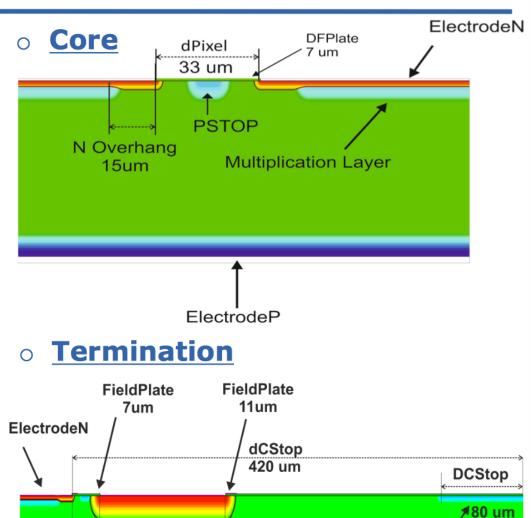




High Granularity Timing Detector (HGTD)

- Two Pixel Size
 - 3000 x 3000 μm²
 - ✓ 2000 x 2000 μm²
- High Resistivity P-Type 50 μm SOI Wafers
- New Run in Progress with 75 and 50 μm
 Epitaxial Wafers









Channel Stop

Extraction Ring

ElectrodeP

WNRing

120um

dNRing

33 um

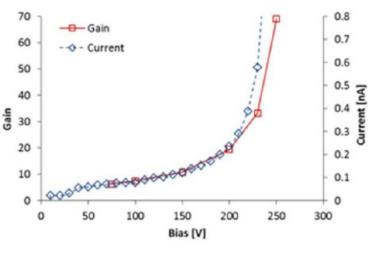
HGTD Sensor Status (last test beam results)

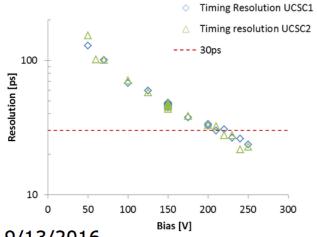
- The 45 µm sensors produced by CNM in the RD50 sponsored Run #9088 validate the principle of thin LGAD as timing detector.
- Timing resolutions of below 30ps were measured in two beam tests with 1.2mm LGAD (single pads).
- A stack of 3 UFSD reached a timing resolution of 15ps. https://arxiv.org/ftp/arxiv/papers/1608/1608.08681.pdf
- LGAD of 1.2mm (single pads) and 3.2mm (2x2 arrays) were produced.
- The stability of operation for small pads is good up to a gain of about 40.

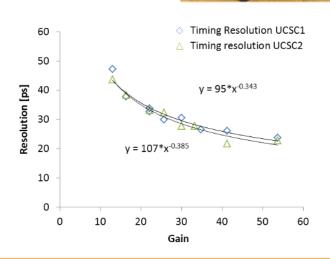
Testing was done by CNM, LPNHE, UCSC, IFAE, Ljubljana, INFN Torino

Gain M = Collected Charge/0.46fC

Good matching of 1mm LGAD Timing resolution ~ M^{-0.36}







planes

Hartmut F.-W. Sadrozinski, HGTD Sensors, 9/13/2016





Telescope frame

Chip Development for High Time Resolution Silicon Detectors

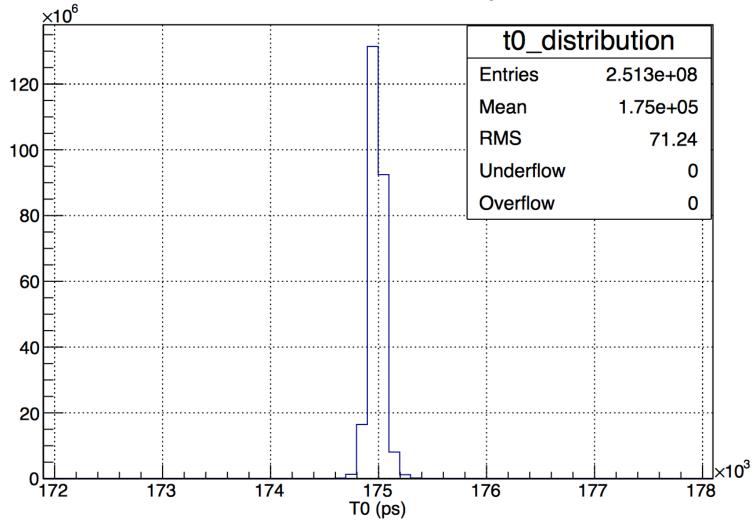
M. Noy

EP-ESE-FE Group, CERN

29th September 2016

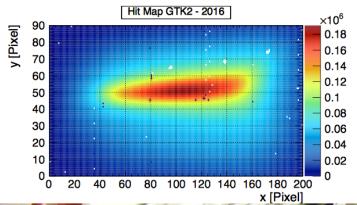
TimeWalk-Corrected (T_0) Time Resolution: Bare ASIC

Distribution of T0 for all pixels

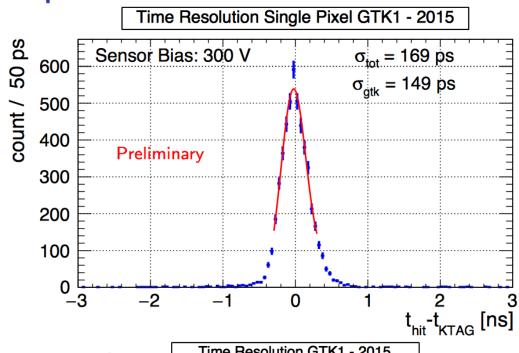


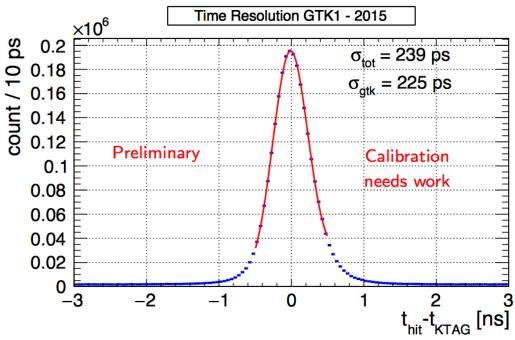
"Whole Chip" Resolution \sim 72 ps RMS

Time Resolution in the Experiment











Time Resolution Synopsis

Time Resolution =
$$\sqrt{\sigma_{electronics+TDC}^2 + \sigma_{WeightingField}^2 + \sigma_{straggling}^2}$$
 = $\sqrt{80^2 + 85^2 + 100^2} \sim 150\,ps$

We will do a beam test with a high spatial resolution telescope to confirm this.

Diamond detector technology: status and perspectives

Harris Kagan for the RD42 Collaboration

Vertex 2016 La Biodola, Isola d'Elba, Italy Sept 28, 2016

Outline of Talk

- The RD42 Program
- Development of Material and Production Capabilities
- Diamond Devices in the LHC and Experiments
- Diamond Device Development 3D Diamond
- Rate Studies
- Summary

3D device in pCVD diamond

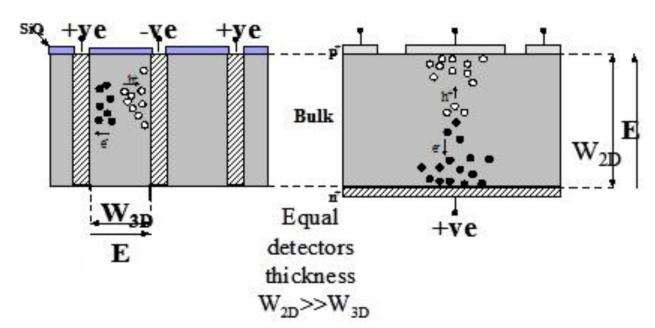


After severe radiation damage all detectors are trap limited

- •Mean free paths $< 75 \mu m$
- ·Would like to keep drift distances smaller than mfp

Comparison of 3D and planar devices

Can one do this in pCVD diamond?



Have to make resistive columns in diamond for this to work

- -columns made with 800nm femtosecond laser
- -initial cells $150\mu m \times 150\mu m$; columns $6\mu m$ diameter

3D device in pCVD diamond



- Measured signal (diamond thickness 500um):
 - Planar Strip ave charge
 6,900e or ccd=192um
 - 3D ave charge 13,500e or ccd_{eq} =350-375um
- For the first time collect >75% of charge in pCVD

